

Fig. 1

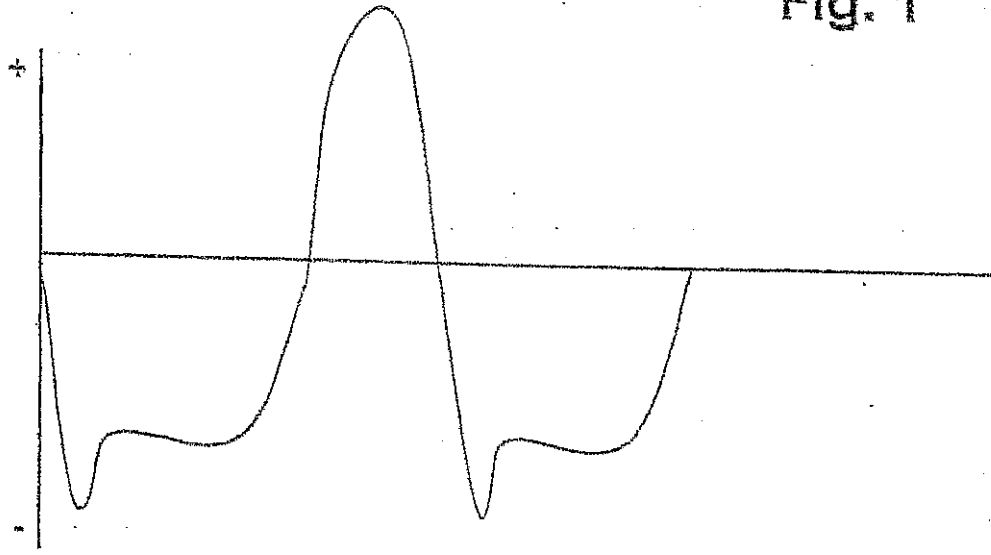


Fig. 2

NiV residual stress and resistivity as a function of RF bias
350-nm film deposited at RT

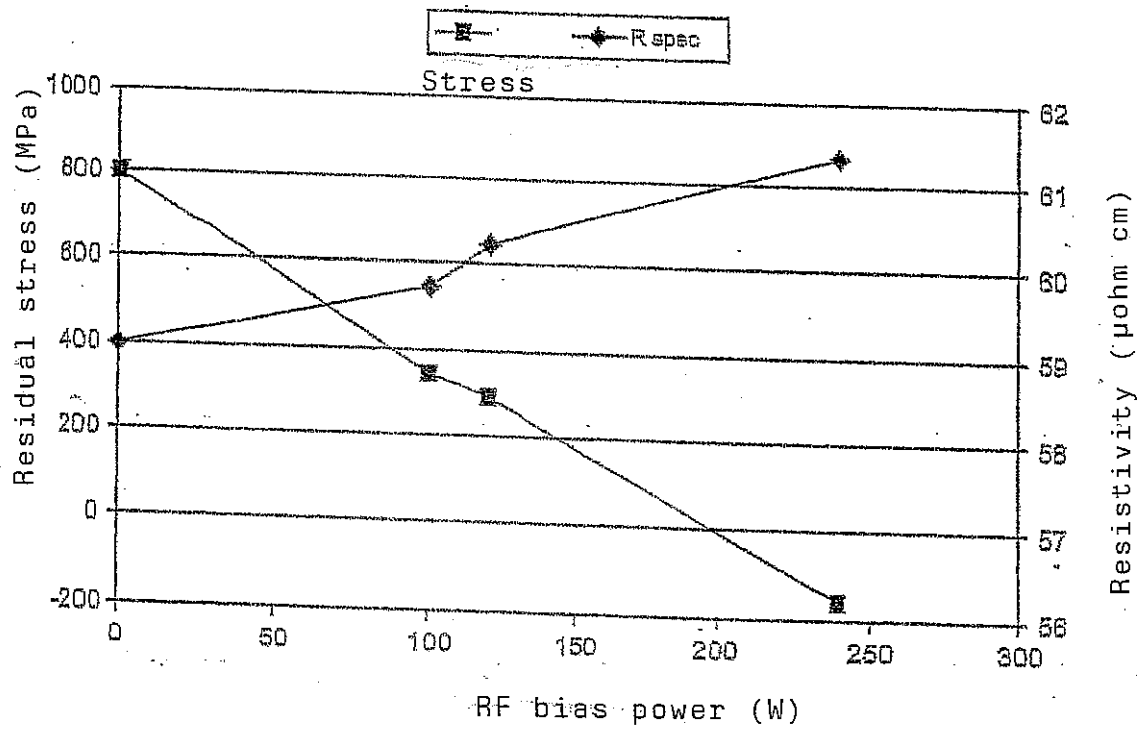


Fig. 3

NiV residual stress as a function of positive pulse voltage

